

ABSTRACT

There is provided an evaporation source for a vacuum evaporation apparatus in which an evaporation direction relative to a film formation object can be arbitrarily set with versatility.

The evaporation source ES₁, ES₂ for use in the vacuum evaporation apparatus DM in vacuum evaporation of a film formation object Sw inside a vacuum chamber Vc has: a main cylindrical body 6 having a crucible part 61 to be filled with an evaporation material Em; a secondary cylindrical body 7 protruded from such a portion of the main cylindrical body 6 as is positioned above the evaporation material; and a heating means 8a capable of heating the evaporation material that is filled in the crucible part. The secondary cylindrical body is detachably mountable on the main cylindrical body while shifting a phase of the discharge opening. A lid body 62 is disposed in a manner to open or close an upper-surface opening 61a of the crucible part. In a state in which the upper-surface opening of the crucible part is blocked by the lid body in a vacuum atmosphere, the evaporation material in the crucible part is heated by the heating means so as to sublime or vaporize the evaporation material. While maintaining the vapor pressure, the sublimated or vaporized evaporation material is arranged to be transferred to the secondary cylindrical body for further discharging out of the discharge opening.